

INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)		Docket Number (Optional) TWI-30261		Application Number NEW 10 621 218	
		Applicant(s) Kenneth Johnson et al.		Filing Date HEREWITH	

### U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
CAT	*AA	4,053,232	10/11/1977	Dill et al.	250	225	04/28/1975
CAT	*AB	4,757,207	07/12/1988	Chappelow et al.	250	491.1	03/03/1987
CAT	*AC	4,999,014	03/12/1991	Gold et al.	356	369	05/04/1989
CAT	*AD	5,166,752	11/24/1992	Spanier et al.	250	201.2	01/11/1990
CAT	*AE	5,293,216	03/18/1994	Moslehi	219	121.6	12/31/1990
CAT	*AF	5,425,964	06/20/1995	Southwell et al.	427	10	07/22/1994
CAT	*AG	5,900,633	05/04/1999	Solomon et al.	250	339.08	12/15/1997
CAT	*AH	6,100,985	08/08/2000	Scheiner et al.	250	341.1	03/12/1999
CAT	*AI	6,281,027	08/28/2001	Wei et al.	438	14	09/11/2000
CAT	*AJ	6,327,035	12/04/2001	Li et al.	356	432	11/30/1999

### FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

### OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

CAT	*AK	W. Kong et al., "A Hybrid Analysis of Ellipsometry Data from Patterned Structures," <i>American Institute of Physics, 1-56396-967-X/01, Characterization and Metrology for ULSI Technology: 2000 International Conference, 2001</i> , pp. 373-377.
CAT	*AL	M.E. Lee et al., "Analysis of Reflectometry and Ellipsometry Data from Patterned Structures," <i>International Conference on Characterization and Metrology for ULSI Technology, Gaithersburg, MD, March 23-27, 1998, AIP Conference Proceedings 449</i> , pp. 331-5, 1998, pp. 1-5.
CAT	*AM	W. Kong et al., "Analysis of Time-Evolved Spectroscopic Ellipsometry Data from Patterned Structures for Etching Process Monitoring and Control," paper 19.2, SRC TECHCON, Las Vegas, Nevada, September 9-11, 1998, 4 pages in length.
CAT	*AN	P.A. Heimann, "Optical Etch-Rate Monitoring Using Active Device Areas: Lateral Interference Effects," <i>J. Electrochem. Soc.</i> , Vol. 132, No. 8, August 1985, pp. 2003-2006.
CAT	*AO	P.A. Heimann et al., "Optical Etch-Rate Monitoring: Computer Simulation of Reflectance," <i>J. Electrochem. Soc.</i> , Vol. 131, No. 4, April 1984, pp. 881-885.
CAT	*AP	H.L. Maynard et al., "Multiwavelength ellipsometry for real-time process control of the plasma etching of patterned samples," <i>J. Vac. Sci. Technol. B</i> , Vol. 15, No. 1, Jan/Feb 1997, pp. 109-115.

Examiner	<i>Craig A. Thompson</i>	Date Considered	<i>5/26/04</i>
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.			